

Docket Number: 081468-0307087
Client Reference: P-0395.010-US



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re the Application of

KLAUS SIMON et al.

Group Art Unit: 1753

Application No.: 10/724,402

Examiner:

Filed: December 1, 2003

Confirmation No.: 8896

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR 1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO-1449. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom. Applicants respectfully request the Examiner return an initialed copy of the enclosed Form PTO-1449 to Applicants with the next Office communication to indicate that the reference(s) has been considered, per MPEP § 609.

This Information Disclosure Statement is being filed before the mailing date of the first Office Action on the merits in the present application. No certification or fee is required.

U.S. Patent No. 5,610,683, U.S. Published Application No. 2002/041420, Cerrina et al. and Singh-Gasson et al. articles were cited in a counterpart foreign application. An English language version of the foreign search report is attached.

The undersigned respectfully notes that copies of U.S. references are not required in applications filed after June 30, 2003.

Respectfully Submitted,

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FORM PTO-1449 (modified)
 To: U.S. Department of Commerce
 (PW FORM PAT-1449)
 Patent and Trademark Office



**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

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	307087	P-0395.010-US
Applicant: SIMON et al.		
Appln. No.: 10/724,402		
Filing Date: December 1, 2003		
Examiner: Unknown	Group Art Unit: 1753	

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
AR	3,573,975	04/1971	Dhaka et al.	117	212	
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					Enclosed	No	Enclose	No
OR	WO 99/49504	09/1999	PCT	Fukami et al.		X		X
PR	EP 0023231	02/1981	Europe	Tabarelli et al.		X		
QR	EP 0418427	03/1991	Europe	Miyake		X		X
RR	EP 1039511	09/2000	Europe	Murakimi et al.		X		X
SR	DD 224448	07/1985	German	Hesse et al.			X	
TR	DD 242880	02/1987	German	Kuch			X	
UR	FR 2474708	07/1981	France	Letellier			X	
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YR	EP Search Report for EP 02258278.7 dated October 22, 2003	
ZR	M. Switkes et al., "Immersion Lithography at 157 nm", MIT Lincoln Lab, Orlando 2001-1, December 17, 2001	
AAR	M. Switkes et al., "Immersion Lithography at 157 nm", J. Vac. Sci. Technol. B., Vol. 19, No. 6, November/December 2001, pp. 2353-2356	
BBR	M. Switkes et al., "Immersion Lithography: Optics for the 50 nm Node", 157 Anvers-1, September 4, 2002	

Examiner

Date Considered:

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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LR	JP 04-305917 /	10/1992	Japan	Ozeki et al.		X		
MR	JP 06-124873 /	05/1994	Japan	Takahashi		X		X
NR	JP 07-220990 /	08/1995	Japan	Fukuda et al.		X		
OR	JP 10-228661 /	08/1998	Japan	Kurokawa		X		
PR	JP 10-255319 /	09/1998	Japan	Suenaga et al.		X		
QR	JP 10-303114 /	11/1998	Japan	Suwa		X		X
RR	JP 10-340846 /	12/1998	Japan	Kudo		X		X
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AR						

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RR	"Depth-of-Focus Enhancement Using High Refractive Index Layer on the Imaging Layer", IBM Technical Disclosure Bulletin, Vol. 27, No. 11, April 1985, p. 6521	/						
SR	A. Suzuki, "Lithography Advances on Multiple Fronts", EEdesign, EE Times, January 5, 2004	/						
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